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	Application No.	Applicant(s)	
Notice of Allowability	09/856,402	NAKANO ET AL.	
	Examiner	Art Unit	-
	Roberts Culbert	1763	
The MAILING DATE of this communication appeal All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this ap or other appropriate communication IGHTS. This application is subject to	plication. If not included n will be mailed in due cour	rse. THIS
1. \boxtimes This communication is responsive to <u>the amendment filed</u>	<u>1/28/05</u> .		
2. The allowed claim(s) is/are <u>1-17</u> .			
3. A The drawings filed on <u>02 October 2001</u> are accepted by th	e Examiner.		
 4. Acknowledgment is made of a claim for foreign priority una) All b) Some* c) None of the: Certified copies of the priority documents have Certified copies of the priority documents have Copies of the certified copies of the priority documents have Copies of the certified copies of the priority do International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 	e been received. e been received in Application No cuments have been received in this of this communication to file a reply	national stage application	
5. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give			CE OF
 CORRECTED DRAWINGS (as "replacement sheets") must (a) including changes required by the Notice of Draftspers 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner's Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in to 7. DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT 	son's Patent Drawing Review (PTO s Amendment / Comment or in the C .84(c)) should be written on the drawing the header according to 37 CFR 1.121(sit of BIOLOGICAL MATERIAL r	Office action of ngs in the front (not the bac (d). must be submitted. Note	·
Attachment(s) 1. ☐ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/O Paper No./Mail Date 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ☐ Interview Summary Paper No./Mail Da 98), 7. ☐ Examiner's Amendr	te	·

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Continued Examination Under 37 CFR 1.114

A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 1/28/05 has been entered.

Allowable Subject Matter

Claims 1-17 are allowed.

The following is a statement of reasons for the indication of allowable subject matter:

The prior art of record fails to teach or render obvious a polishing machine for a peripheral edge of a semiconductor wafer comprising: a rotary mechanism for holding a semiconductor wafer while rotating it in a prescribed direction; a rotary body which rotates relative to the semiconductor wafer while maintaining a prescribed gap from a periphery of the semiconductor wafer, having a rotary axis which is set in the same direction as the rotary axis of the semiconductor wafer so that the rotary body and the semiconductor wafer are not in contact with each other during a complete polishing process; a polishing solution channel for channeling the flow of polishing solution to the gap and a polishing solution supply portion for supplying the polishing solution to the polishing solution channel; wherein the polishing solution is drawn into the gap between the peripheral edge of the semiconductor wafer and the rotary body, and polishing abrasive particles in the polishing solution collide with the peripheral edge the semiconductor wafer to conduct non-contact polishing of the peripheral edge of the semiconductor wafer.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Roberts Culbert whose telephone number is (571) 272-1433. The examiner can normally be reached on Monday-Friday (7:30-4:00).

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor,

Gregory Mills can be reached on (571) 272-1439. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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